IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q89627

Koichi TERASHIMA, et al. Appln. No.: 10/544,783

Group Art Unit: 1722 Examiner: Pape A. SENE

Confirmation No.: 5339 Filed: August 8, 2005

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MÉTHOD FOR FORMING NICKEL SILICIDE FILM, METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICE, AND METHOD FOR ETCHING NICKEL SILICIDE

PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. § 1.136, Applicant hereby petitions for an extension of time of one month, extending the time for responding to the Office Action of February 12, 2008 to April 12, 2008.

The statutory fee of \$120.00 is being submitted via EFS. The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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WASHINGTON OFFICE 23373
CUSTOMER NUMBER

Date: April 11, 2008

Howard L. Bernstein Registration No. 25,655